



PATENT
3811-0122P

IN THE U.S. PATENT AND TRADEMARK OFFICE

Applicant: Yi Yeol LYU et al. Conf.: 4059

Appl. No.: 10/621,380 Group: 1712

Filed: July 18, 2003 Examiner: M. G. MOORE

For: SILOXANE-BASED RESIN AND METHOD FOR
FORMING INSULATING FILM BETWEEN
INTERCONNECT LAYERS IN SEMICONDUCTOR
DEVICES BY USING THE SAME

LARGE ENTITY TRANSMITTAL FORM

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

February 4, 2005

Sir:

Transmitted herewith is a response to notice of non-compliant amendment in the above-identified application.

- The enclosed document is being transmitted via the Certificate of Mailing provisions of 37 C.F.R. § 1.8.
- The enclosed document is being transmitted via facsimile.

The fee has been calculated as shown below:

	CLAIMS REMAINING AFTER AMENDMENT	HIGHEST NUMBER PREVIOUSLY PAID FOR			PRESENT EXTRA	RATE	ADDITIONAL FEE
TOTAL	12	-	20	=	0	\$50	\$0.00
INDEPENDENT	2	-	3	=	0	\$200	\$0.00
<input type="checkbox"/> FIRST PRESENTATION OF A MULTIPLE DEPENDENT CLAIM						\$360	\$0.00
						TOTAL	\$0.00

- Petition for () month(s) extension of time pursuant to 37 C.F.R. §§ 1.17 and 1.136(a). \$0.00 for the extension of time.
- No fee is required.
- Check(s) in the amount of \$0.00 is(are) enclosed.
- Please charge Deposit Account No. 02-2448 in the amount of \$0.00. This form is submitted in triplicate.

If necessary, the Commissioner is hereby authorized in this, concurrent, and future replies, to charge payment or credit any overpayment to Deposit Account No. 02-2448 for any additional fees required under 37 C.F.R. § 1.16 or under 37 C.F.R. § 1.17; particularly, extension of time fees.

Respectfully submitted,

BIRCH, STEWART, KOLASCH & BIRCH, LLP

By Robert E. Guayzen #42,593
for Joseph A. Kolasch, #22,463

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JAK/REG:jls
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Attachment(s)



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IN THE U.S. PATENT AND TRADEMARK OFFICE

Applicant: Yi Yeol Lyu et al. Conf.: 4059
Appl. No.: 10/621,380 Group: 1712
Filed: July 18, 2003 Examiner: Margaret G. Moore
For: SILOXANE-BASED RESIN AND METHOD FOR
FORMING INSULATING FILM BETWEEN
INTERCONNECT LAYERS IN SEMICONDUCTOR
DEVICES BY USING THE SAME

RESPONSE TO NOTICE OF NON-COMPLIANT AMENDMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

February 4, 2005

Sir:

In reply to the Notice of Non-Complaint Amendment mailed January 28, 2005, the following amendments and remarks are respectfully submitted in connection with the above-identified application.

This reply includes a substitute claim set and remarks.